

AMENDMENTS TO THE CLAIMS:

Please amend the claims as follows:

1. (Currently Amended) A liquid crystal display (LCD), comprising:
 - a gate line formed on a transparent substrate, ~~edges of said gate line being substantially straight and even;~~
 - a data line crossing said gate line and formed on said transparent substrate, ~~edges of said data line being substantially straight and even;~~
 - an insulating layer electrically insulating said data line from said gate line;
 - a thin film transistor formed at an intersection of said gate line and said data line, and connected to said gate line and said data line;
 - a passivation layer formed over the thin film transistor;
 - a pixel electrode having portions thereof formed on the surface of the passivation layer, but not over the thin film transistor; and
 - a low reflective layer formed on at least a portion of at least one of said gate line and said data line; and
 - an upper substrate located above the pixel electrode, wherein an area between said pixel electrode and said upper substrate, and above said low reflective layer, is free of any black matrix or light shielding layer.
2. (Original) The LCD of claim 1, wherein said low reflective layer is formed on a portion of said gate line.

3. (Previously Presented) The LCD of claim 2, wherein said low reflective layer is formed on said gate electrode.

4. (Original) The LCD of claim 3, wherein said thin film transistor includes a source electrode and a drain electrode; and
said low reflective layer is formed on said source and drain electrodes.

5. (Original) The LCD of claim 4, wherein said low reflective layer has a light reflectivity of 3% or less.

6. (Original) The LCD of claim 4, wherein said low reflective layer is formed of CrOx.

7. (Original) The LCD of claim 1, wherein
said thin film transistor includes a gate electrode connected to said gate line; and
said low reflective layer is formed on said gate electrode.

8. (Original) The LCD of claim 1, wherein said thin film transistor includes a source electrode and a drain electrode; and
said low reflective layer is formed on said source and drain electrodes.

9. (Original) The LCD of claim 1, wherein said low reflective layer has a light reflectivity of 3% or less.

10. (Original) The LCD of claim 1, wherein said low reflective layer is formed of CrOx.

11. (Previously Presented) The LCD of claim 1, wherein said passivation layer formed over said gate line, said data line, said low reflective layer and said pixel electrode formed on said passivation layer is connected via a contact hole in said passivation layer to said thin film transistor.

12. (Original) The LCD of claim 11, wherein said pixel electrode is formed over a portion of said data line.

13. (Original) The LCD of claim 11, wherein said pixel electrode is formed over a portion of said gate line.

14. (Original) The LCD of claim 11, further comprising:
a color filter substrate with color filters formed thereon; and
liquid crystal sealed between said color filter substrate and said transparent substrate.

15. (Currently Amended) A method of manufacturing a liquid crystal display, comprising:

forming a gate line and a portion protruding from said gate line to serve as a gate electrode of a thin film transistor on a transparent substrate, ~~edges of said gate line being substantially straight and even~~;

forming an insulating layer electrically insulating said gate line;

forming a data line over said transparent substrate and crossing said gate line, ~~edges of said data line being substantially straight and even~~;

forming a passivation layer over the thin film transistor;

forming a pixel electrode with portions thereof on the surface of the passivation layer, but not over the thin film transistor; and

first forming a low reflective layer over at least a portion of at least one of said gate line and said data line;:

forming an upper substrate above the pixel electrode, wherein an area between said pixel electrode and said upper substrate, and above said low reflective layer, is free of any black matrix or light shielding layer

16. (Original) The method of claim 15, further comprising:

second forming a low reflective layer over said gate line.

17. (Previously Presented) The method of claim 16, wherein said second forming step forms said low reflective layer over said gate electrode.

18. (Original) The method of claim 15, wherein said forming a gate line step forms a portion protruding from said gate line to serve as a gate electrode of a thin film transistor; and further including,

second forming a low reflective layer over said gate electrode.

19. (Original) The method of claim 15, wherein said forming a data line step forms a portion protruding from said data line to serve as a source electrode of a thin film transistor; and

 said first forming step forms said low reflective layer over said source electrode.

20. (Original) The method of claim 15, wherein said low reflective layer has a light reflectivity of 3% or less.

21. (Original) The method of claim 15, wherein said low reflective layer is formed of CrOx.

22. (Currently Amended) A method of manufacturing a liquid crystal display, comprising:

forming a gate line and gate electrode connected thereto on a transparent substrate, ~~edges of said gate line being substantially straight and even;~~

forming an insulating layer over said gate line and gate electrode;

forming a semiconductor layer over said gate electrode;

forming a data line crossing said gate line, ~~edges of said data line being substantially straight and even~~, a source electrode connected to said data line and on a first portion of said semiconductor layer, and a drain electrode on a second portion of said semiconductor layer;

forming a low reflective layer over at least a portion of at least one of said gate line and said data line;

forming a passivation layer having a contact hole exposing said drain electrode over said transparent substrate; and

forming a pixel electrode with portions thereof disposed on said passivation layer but not over the thin film transistor, and connected to said drain electrode via said contact hole; and

forming an upper substrate above the pixel electrode, wherein an area between said pixel electrode and said upper substrate, and above said low reflective layer, is free of any black matrix or light shielding.

23. (Original) The method of claim 22, wherein said forming a pixel electrode step forms said pixel electrode to overlap a portion of said data line.

24. (Original) The method of claim 22, wherein said forming a pixel electrode step forms said pixel electrode to overlap a portion of said gate line.

25. (Currently Amended) The method of claim 22, further comprising:
forming a color filter on a color filter substrate; and
sealing the liquid crystal between said color filter substrate and said transparent substrate.